

ATOMIC LAYER DEPOSITION

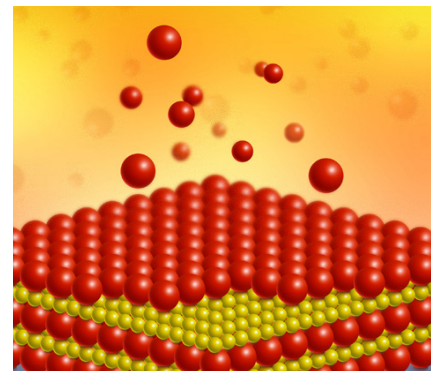
THE OPPORTUNITY

Atomic layer deposition was invented more than 40 years ago and has recently been deemed as one of the critical enabling technologies in the advanced nodes in semiconductor manufacturing industry.

In general, if substrate temperature is too low, the half-reaction could be incomplete. If the substrate temperature is high, desorption or decomposition can occur. To accurately realize the recipe temperature set points, carefully designed and implemented thermal instrumentation is required.

OUR SOLUTION

Advanced Energy offers two solutions. The first is a fiber optic temperature monitoring solution based on the Luxtron® Fluoroptic® technology. This solution uses a fiber optic probe that is immune to plasma interference and has a temperature range of -100 to 330°C. The other is a fiber optic radiation pyrometer and typically is used for temperature range above 50°C but can handle very high temperatures.



YOUR BENEFITS

- Enhanced yield
- Better quality
- Works in plasma enhanced system



For international contact information,
visit advancedenergy.com.

sales.support@aei.com
+1 970 221 0108

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